

Application No. 09/449,907
Attorney Docket No. 107176-09004

the workpiece for polishing the same and disposed in a first plane;
polishing agent passages, having bottoms disposed in a second plane, for
introducing a polishing agent; and
B1
CONC a plurality of one-stage step portions formed between said polishing faces of said
polishing projections and the bottoms of said polishing agent passages and disposed in
a third plane, the first, second and third planes spaced apart from and extending
parallel to one another.

54. (Once Amended) A chemical mechanical polishing apparatus,
comprising:
a chemical mechanical polishing cloth for chemically mechanically polishing a
workpiece;
a polishing head for holding and rubbing a workpiece with said chemical
mechanical polishing cloth; and
a polishing agent supply mechanism for supplying a polishing agent to said
chemical mechanical polishing cloth,
B2 said chemical mechanical polishing cloth including, on an opposite-to-
workpiece face thereof:
polishing projections having polishing faces arranged to come in contact with
the workpiece for polishing the same and disposed in a first plane;
polishing agent passages, having bottoms disposed in a second plane, for
introducing a polishing agent; and
a plurality of one-stage step portions formed between said polishing faces of
said polishing projections and the bottoms of said polishing agent passages and